

ABSTRACT OF THE DISCLOSURE

In a method of manufacturing a metal pattern, a metal layer is deposited on a passivation layer, and a photoresist pattern is then formed on the metal layer. Using the photoresist pattern as a mask, an exposed portion of the metal layer is treated with a plasma to lower a binding force in the metal. The metal layer is then etched to form a metal pattern. The method is applicable to the formation of pixel electrodes in LCD devices.